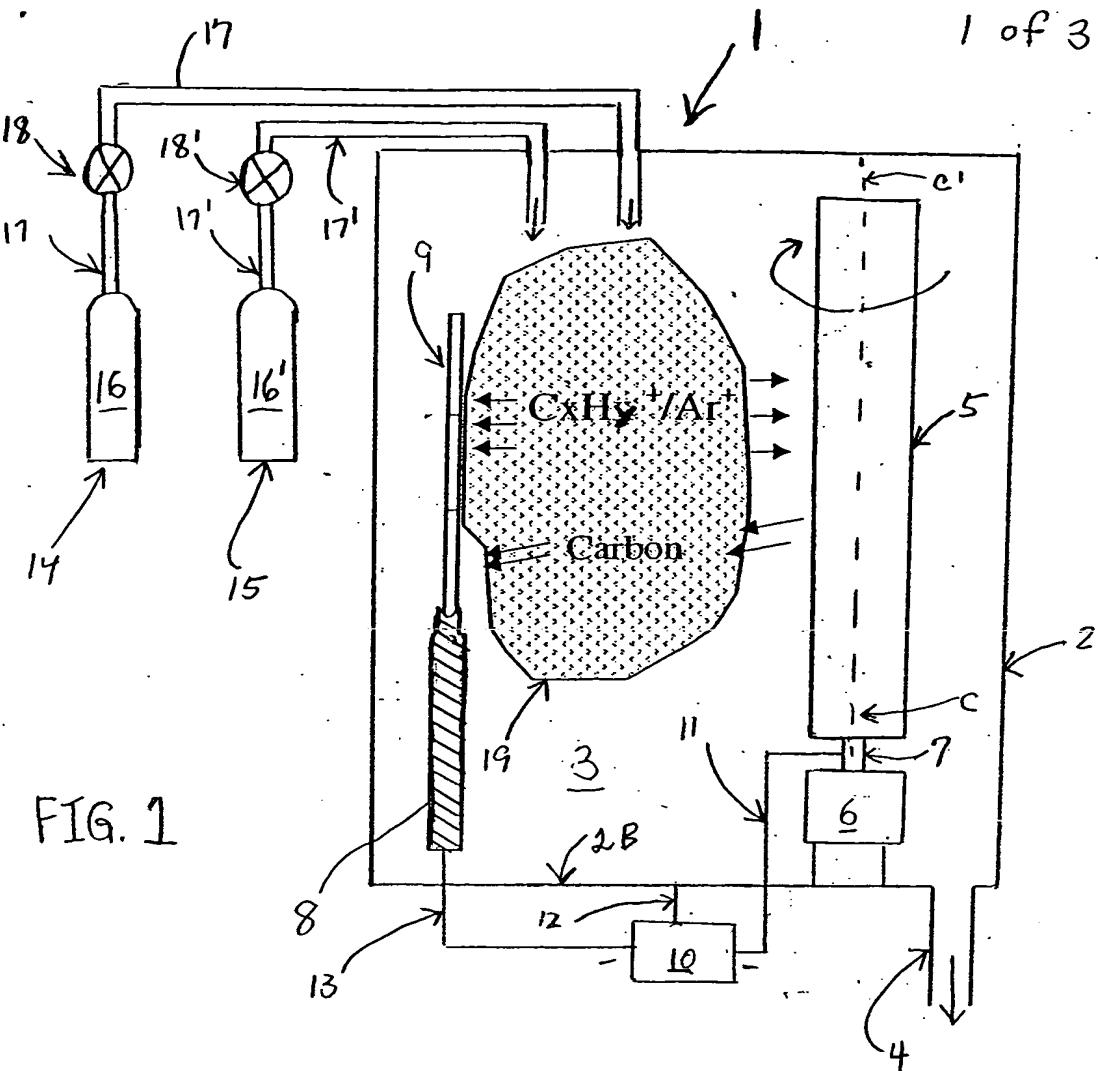


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Percentage Deposited Carbon from C₂H₂ vs C₂H₂ Flow
(Ar flow=146sccm, Pressure -2.7mTorr)

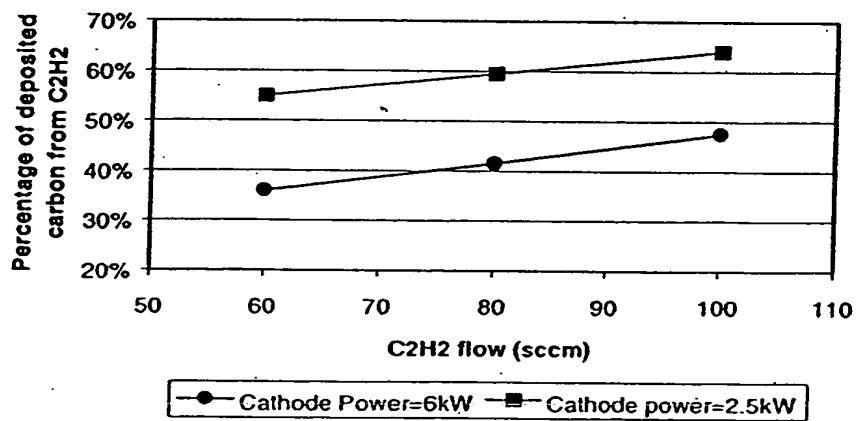


FIG. 2

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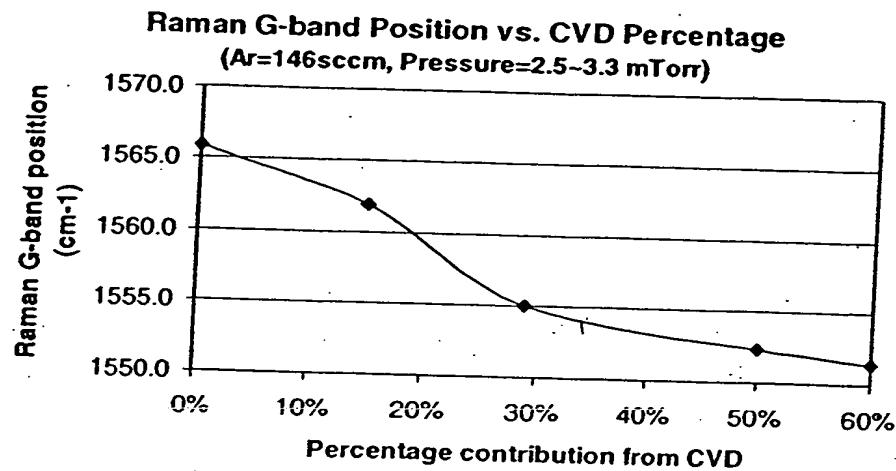


FIG. 3

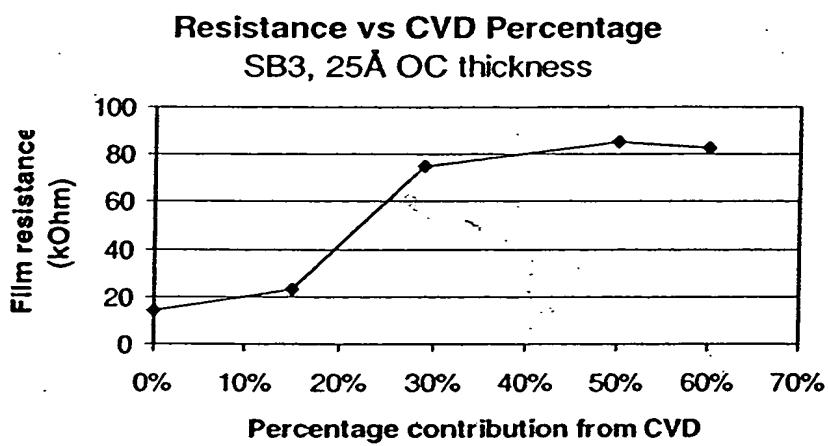


FIG. 4

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Surface Mark vs C₂H₂ Contribution (F104026)

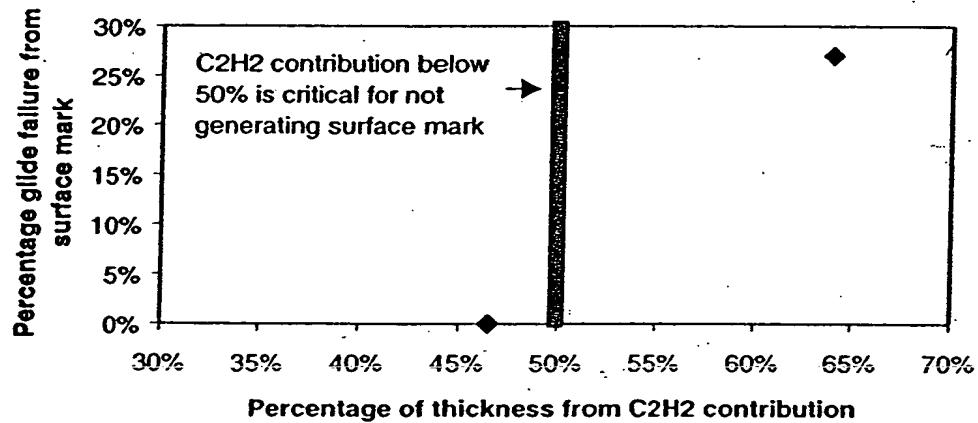


FIG. 5

CoOx Comparison of CVD-assisted Carbon and Sputter Carbon (After 4 days 80C/80%RH stress)

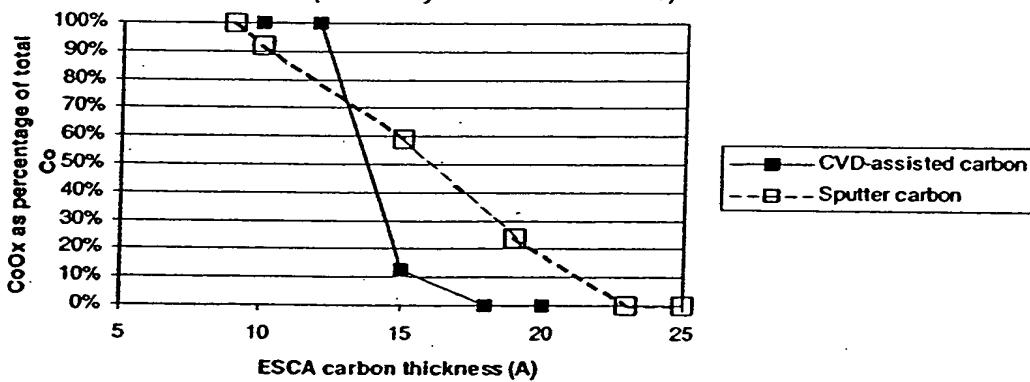


FIG. 6